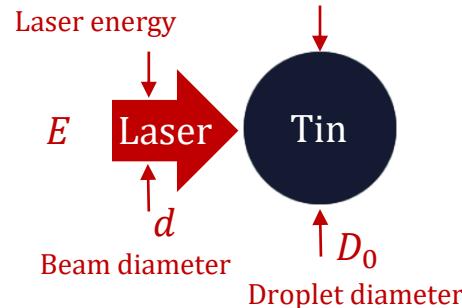


Tailoring the expansion-to-propulsion ratio of laser-induced tin targets for EUV nanolithography

J. Hernandez-Rueda, B. Liu, D. J. Hemminga, Y. Mostafa, R. A. Meijer, J. Sheil and O. O. Versolato
EUV Plasma Processes group, Amsterdam

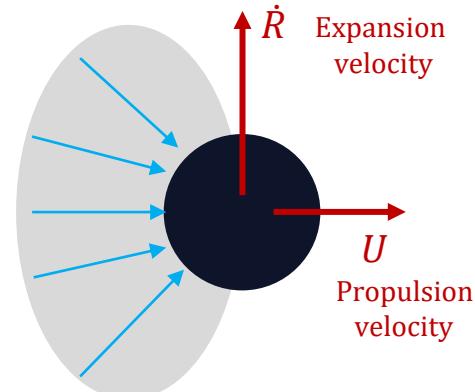
Laser-tin interaction



How do experimental parameters influence the kinetic energy partition?

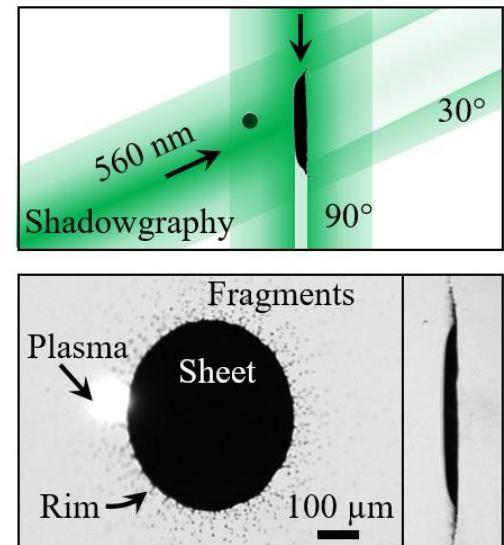
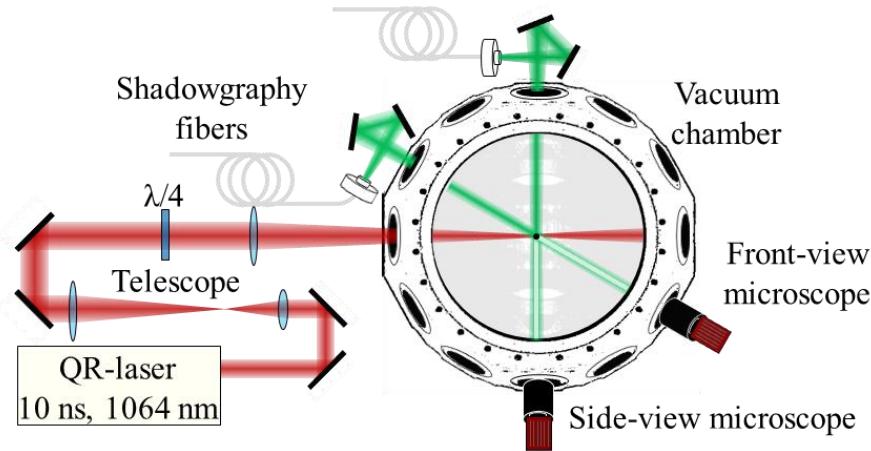
Link light-matter interaction to plasma expansion and to early hydrodynamic response.

Early hydrodynamics





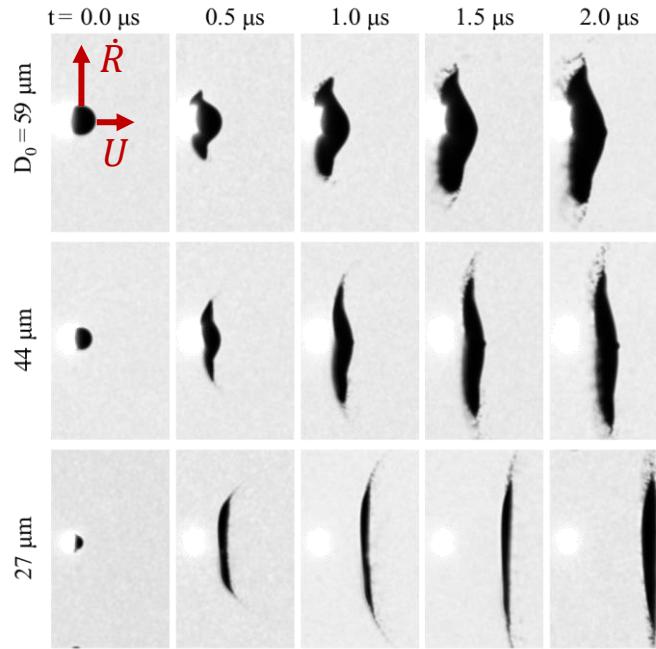
Experimental method and parameters explored



- We explore a large parameter space: tin droplet diameter D_0 , laser beam diameter d and energy E .



Experimental results: morphology, propulsion velocity and radial expansion rate



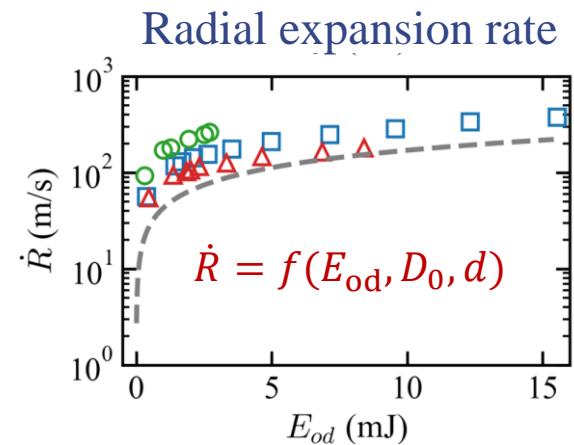
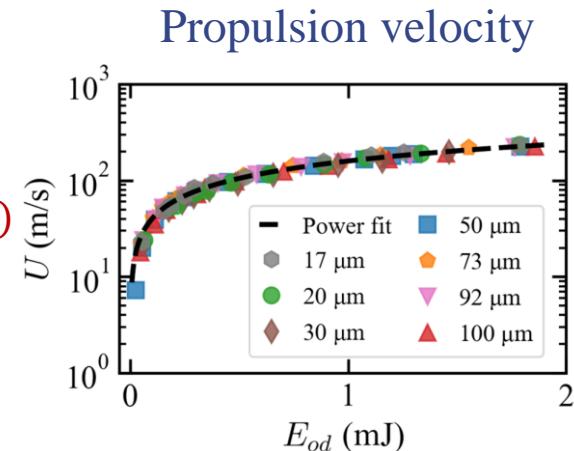
$$U = K_U E_{\text{od}}^\alpha$$

$$U = f(E_{\text{od}}, D_0)$$



$$\dot{R}_0 > U$$

- Smaller d/D_0 ratios lead to targets with larger curvature.
- $U-E_{\text{od}}$ data collapse on a single curve for a given D_0
- U data can be predicted by a function of E_{od} and D_0 .
- Tighter beams lead to larger \dot{R}_0 .





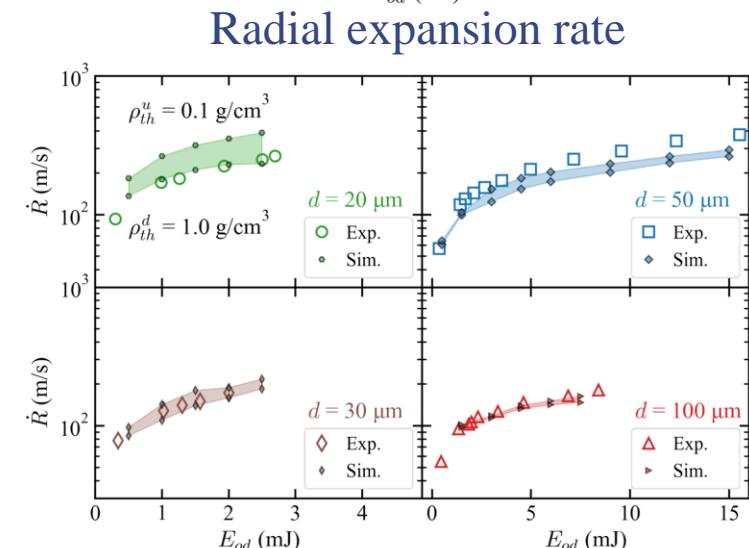
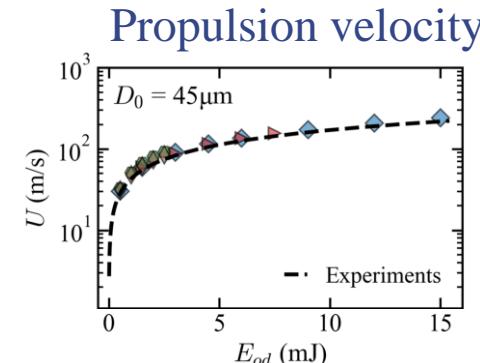
RALEF 2D results: comparison of simulations with experiments (using U and \dot{R})

Input parameters: $\tau_p = 10$ ns, $\lambda = 1064$ nm, d , D_0 and E .

Output: velocity field, mass distribution, temperature, pressure, kinetic energy...and U and \dot{R}



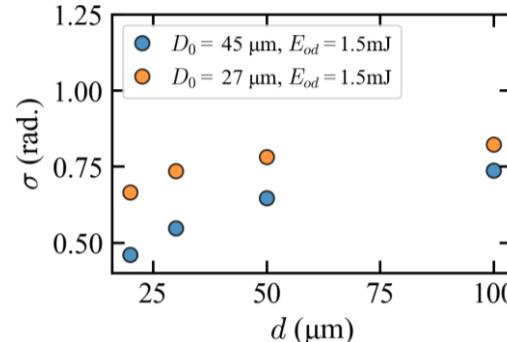
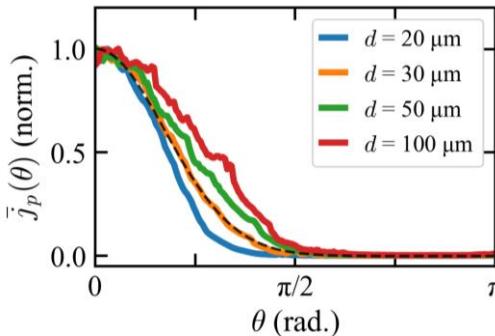
Experiments and simulations in reasonable agreement!!



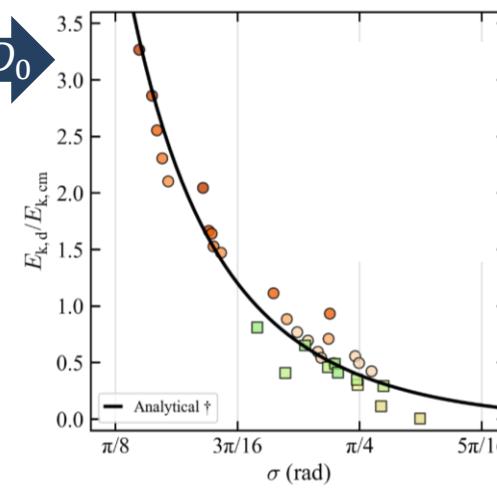
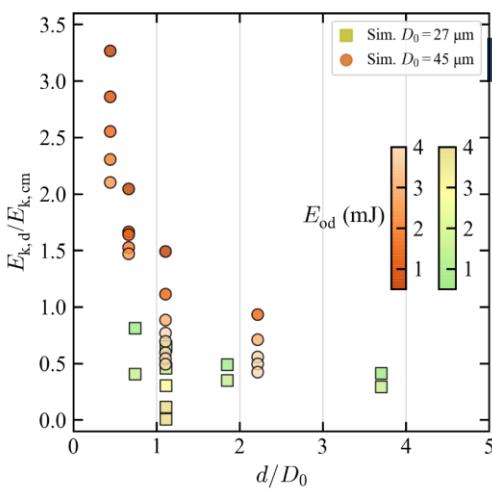


Pressure impulse influence on the kinetic energy partitioning

Pressure impulse profiles



Kinetic energy partitioning



Pressure impulse width σ

- Gaussian is a good approximation
- Strong dependence with beam size
- Minor dependence with energy

- The width σ can be used as the sole parameter to extract the kinetic energy partitioning.

$$E_{k,d}/E_{k,cm} = f(d, E, D_0) = f(\sigma)$$

- The simulated energy partition is in excellent correspondence with analytical fluid-dynamics model



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Total staff currently involved in Source:

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2 technicians; (3 vacancies)

